

CERTIFICATE OF MAILING BY FIRST CLASS MAIL (37 CFR 1.8)

Applicant(s): Yasushi AKIYAMA et al.

Docket No.

2002JP311

Serial No.

10/519,242

Filing Date

December 22, 2004

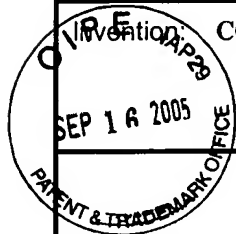
Examiner

WU, Ives J.

Group Art Unit

1713

COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME

I hereby certify that this English Language abstract of JP 60-0263141 - 1 Page

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PATENT ABSTRACTS OF JAPAN

(11)Publication number : 60-263141

(43)Date of publication of application : 26.12.1985

(51)Int.Cl. G03C 1/00

G03F 7/00

(21)Application number : 59-120567 (71)Applicant : FUJI PHOTO FILM CO LTD

(22)Date of filing : 12.06.1984 (72)Inventor : KOIKE MITSURU

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TOYAMA TADAO

(54) PHOTOPOLYMERIZABLE SENSITIVE MATERIAL

(57)Abstract:

PURPOSE: To enhance storage stability under high temp. and high humidity by forming a protective layer made of a specified org. polymer and an acid.

CONSTITUTION: A photopolymerizable layer and the protective layer transmitting activated rays and substantially impermeable to oxygen and made of a polymer and an acid are laminated on a support in succession. Since PVA and a mixture of PVA and carboxymethyl cellulose are superior in impermeability to O₂, they are suitable for said polymer, and as said acid, mineral acids and org. acids, preferably, such as malic acid, tartaric acid, the 2-methoxy-4-hydroxy-5-benzoylbenzenesulfonic acid, are used. Both components are dissolved in water or a solvent, such as methanol, to prepare a coating material and the protective layer is formed by coating the photopolymerizable sensitive layer.

LEGAL STATUS [Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]